

	Hits	Search Text	DBs
37	1	\$4lithograph\$5 and ((support or hold or stage) same (expos\$4 or illuminat\$4 or irradiat\$4) same (mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and project\$4 and ((mask or reticle or pattern\$4 or photomask) same (shield\$4 or absorb\$4 or ((multi\$4layer or alternat\$4) near5 (stack or layer)) or (low near4 index near9 high near9 alternat\$4))) and ((absorb\$4 or shield\$4 or antireflect\$4) same (multi\$3layer or stack or (alternat\$5 near3 layer) or (pluralit\$4 near3 layer)) same ((pattern\$6 near16 device) or photomask or mask or reticle) same ((reduc\$5 or minimi\$6 or chang\$5 or decreas\$4) near22 aberrat\$6))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
38	184	\$4lithograph\$5 and ((support or hold or stage) same (expos\$4 or illuminat\$4 or irradiat\$4) same (mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and project\$4 and ((mask or reticle or pattern\$4 or photomask) same (shield\$4 or absorb\$4 or ((multi\$4layer or alternat\$4) near5 (stack or layer)) or (low near4 index near9 high near9 alternat\$4))) and ((absorb\$4 or shield\$4 or antireflect\$4) same (multi\$3layer or stack or (alternat\$5 near3 layer) or (pluralit\$4 near3 layer)) same ((pattern\$6 near16 device) or photomask or mask or reticle))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
39	39	\$4lithograph\$5 and ((support or hold or stage) same (expos\$4 or illuminat\$4 or irradiat\$4) same (mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and project\$4 and ((mask or reticle or pattern\$4 or photomask) same (shield\$4 or absorb\$4 or ((multi\$4layer or alternat\$4) near5 (stack or layer)) or (low near4 index near9 high near9 alternat\$4))) and ((absorb\$4 or shield\$4 or antireflect\$4) same ((pattern\$6 near16 (structure or device)) or photomask or mask or reticle) same (improv\$4 near26 contrast))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
40	1	\$4lithograph\$5 and ((support or hold or stage) same (expos\$4 or illuminat\$4 or irradiat\$4) same (mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and project\$4 and ((mask or reticle or pattern\$4 or photomask) same (shield\$4 or absorb\$4 or ((multi\$4layer or alternat\$4) near5 (stack or layer)) or (low near4 index near9 high near9 alternat\$4))) and ((absorb\$4 or shield\$4 or antireflect\$4) same (multi\$3layer or stack or (alternat\$5 near3 layer) or (pluralit\$4 near3 layer)) same (('pattern\$6 near16 device) or photomask or mask or reticle) same (((reduc\$5 or minimi\$6 or chang\$5 or decreas\$4) near22 aberrat\$6) or (improv\$4 near26 contrast)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
41	0	\$4lithograph\$5 and ((support or hold or stage) same (expos\$4 or illuminat\$4 or irradiat\$4) same (mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and project\$4 and ((mask or reticle or pattern\$4 or photomask) same (shield\$4 or absorb\$4 or ((multi\$4layer or alternat\$4) near5 (stack or layer)) or (low near4 index near9 high near9 alternat\$4))) and ((absorb\$4 or shield\$4 or antireflect\$4) same (multi\$3layer or stack or (alternat\$5 near3 layer) or (pluralit\$4 near3 layer)) same ((pattern\$6 near16 (structure or device)) or photomask or mask or reticle) same (improv\$4 near26 contrast))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB